

IN THE CLAIMS:

Please CANCEL claims 1-10, 19 and 20 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 11 and 14-18, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-10. (Canceled)

11. (Currently Amended) An exposure method of projecting a pattern ~~[[on]]~~ of an original onto a substrate, said method comprising steps of:

measuring a position of an alignment mark formed on the substrate;

projecting the pattern onto the substrate based on a measurement result in said measurement step; and

projecting onto the substrate, based on the measurement result, a mark, which has a known relative position from a reference pattern arranged on an original stage and to align the original stage and a substrate stage, and is arranged on the original stage and to form an alignment mark on the substrate.

12. (Original) A method according to claim 11, further comprising a step of controlling a position of the original stage and a position of the substrate stage based on the measurement result.

13. (Original) A method according to claim 12, wherein in said control step, the position of the original stage and the position of the substrate stage are so controlled as to project the mark in a region which is in a peripheral region of the substrate and outside a region where the pattern is projected.

14. (Currently Amended) A method according to claim 11, wherein ~~the marks of a~~ plurality of kinds of the mark are arranged on the original stage.

15. (Currently Amended) A method according to claim 14, wherein the plurality of kinds of the mark ~~includes~~ include an identification mark for identifying ~~the kind~~ one of the plurality of kinds of the mark.

16. (Currently Amended) A method according to claim 11, wherein the ~~marks of a~~ plurality of kinds of the mark are arranged on the original stage, and in said measurement step, a position of the alignment mark formed on the substrate is measured based on the kind.

17. (Currently Amended) A method according to claim 16, wherein in said measurement step, a position of an alignment mark of a second kind of the plurality of kinds of the mark is measured based on a position of an alignment mark of a first kind of the plurality of kinds of the mark.

18. (Currently Amended) A software for causing a computer to control execution of an exposure method as defined in claim 11.

19-20. (Canceled)